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U.S. UTILITY Patent Application

SCANNED

O.I.P.E.

PATENT DATE

APPLICATION NO. 09/964648	CONT/PRIOR F	CLASS 438 700	SUBCLASS 121	ART UNIT 2812 21251	EXAMINER CABRER
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Keiji Yoshimura

APPLICANTS

Exposure apparatus, semiconductor device
manufacturing method,
exposure apparatus
maintenance method and semiconductor
manufacturing factory

PTO-2040
12/99

ISSUING CLASSIFICATION

ORIGINAL		CROSS REFERENCE(S)					
CLASS	SUBCLASS	CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)				
INTERNATIONAL CLASSIFICATION							

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TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed.	(Assistant Examiner) _____ (Date) _____			NOTICE OF ALLOWANCE MAILED	
<input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S Patent. No. _____ _____ _____	(Primary Examiner) _____ (Date) _____			ISSUE FEE	
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